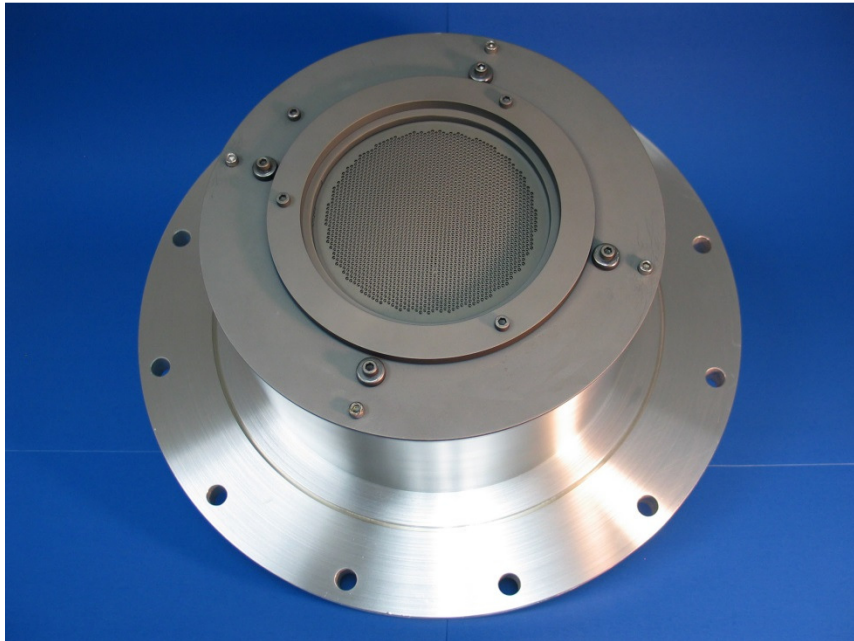




plasma process group

12 cm RF Ion Beam Source



Features

- **RF Discharge (no filament)**
- **Multiple Available Beam Shapes**
- **Variety of Process Gases**
- **Versatile Power Range**
- **Easy Maintenance**

Applications

- **Sputter Deposition**
- **Etching**
- **Ion Beam-Assisted Deposition**
- **Materials Research**

Description

Plasma Process Group offers a 12 cm RF ion beam source for research and manufacturing environments, ideal for assist or deposition applications. Using RF discharge (no filaments) minimizes maintenance requirements and allows for a wider range of process gases including many reactive species.

New technology developed by Plasma Process Group has dramatically extended the operating life of RF sources in conductive deposition and etching, making RF a good choice for all types of processes.

Whether you're in research or production, Plasma Process Group is committed to providing the best support possible. Help is just a phone call away (or email if you prefer). Our people have many years of experience with ion beam sources, systems, and applications, and we're happy to share that with you. Give us a call.

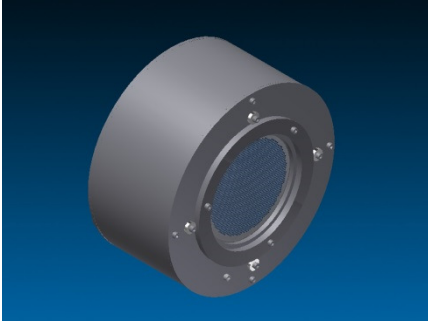
Molybdenum, Titanium, and Pyrolytic Graphite, grids are available for the 12 cm ion beam source allowing for a variety of deposition and etching process requirements. RF ion beam sources are typically flange-mounted, but custom mounting is available. Grid assemblies can be custom designed to shape the beam for your specific substrate and vacuum chamber geometry.

We understand that every ion beam installation is unique and we're ready to discuss the requirements of your specific application.

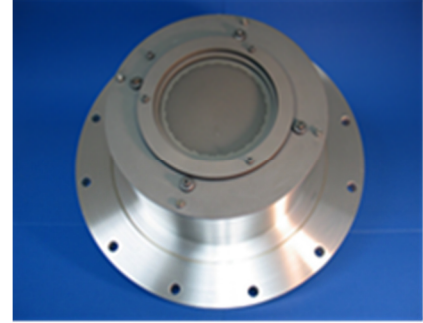
Specifications

12 cm Source

Internal Mount

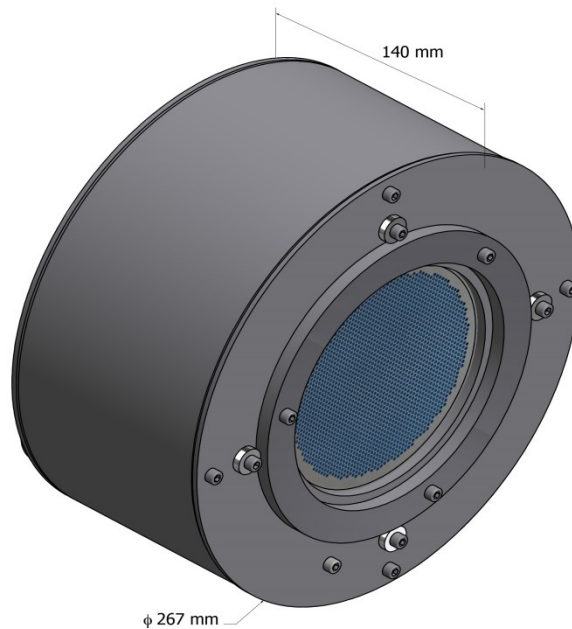


Flange Mount (14" CF)



Ion source	12 cm RF
Model number	12RF08
Beam size at grids	12 cm
Beam current	50-400 mA
Beam energy	100-1500 eV
Grid material	Molybdenum or Pyrolytic Graphite
Beam neutralization	RF Neutralizer (sold separately)
Cooling	Water-Cooled Antenna and Shroud
Power supply	I-BEAM™ 703
Weight	6.8 Kg (15 lbs.)

Dimensions



Ordering Information: The 12 cm Ion beam source is available with options such as flange or internal mounting kits to facilitate installation. A variety of grid designs are available for your output ion beam. Please contact us to configure your ion source.

Suggested Accessories:

IBEAM 703 I-BEAM™ 703 RFS/RFN Power Supply with built-in 500W RF generator
504424B RF Neutralizer
504552A / 504553A ATN-10 Matching Network for source / PT-II Auto Controller for Matching Network



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